

# NPTEL Assignment

## Week-3

1. Select Correct statements from the following statements:

- i) The Noise margin corresponding to the higher voltage level is defined as  $NM_H = V_{OH} - V_{IH}$
- ii) The Noise margin corresponding to the higher voltage level is defined as  $NM_H = V_{IH} - V_{OH}$
- iii) The Noise margin corresponding to the lower voltage level is defined as  $NM_L = V_{OL} - V_{IL}$
- iv) The Noise margin corresponding to the lower voltage level is defined as  $NM_L = V_{IL} - V_{OL}$

- 1. Only i, ii, iii
- 2. Only i
- 3. Only ii, iii
- 4. Only iv
- 5. **Only i, iv**
- 6. Only iii
- 7. Only i, iii
- 8. All of the above

2. For an unskewed inverter of size 4:2 as P:N, what is the  $NM_H$  and  $NM_L$  value for a 65 nm technology node with rail voltage of 1V ?

- 1. 100,100 mV
- 2. 50,50 mV
- 3. 550,550 mV
- 4. 500,500 V
- 5. 400,450 V
- 6. 450,400 mV
- 7. 450,500 mV
- 8. **400,400 mV**

$V_{out} = \begin{cases} V_{OL} = 0.05V \\ V_{IH} = 0.55V \end{cases}$

Similarly,  
 $I_{sd}$   
 p mos  
 Linear

$\begin{cases} V_{OH} = 0.95V \\ V_{IL} = 0.45V \end{cases}$

### Solution:-

3. If the inverter circuit for a rail voltage of 1V is characterized to have noise signal below 0.5V with ideally zero static current, and no overhead clock signal, the designers are likely to use the following designs?

1. **High-Skew Inverter**
2. Low-Skew Inverter
3. 2:1 Un-skewed Inverter
4. Higher Widths of Un-skewed Inverter
5. Asymmetric design
6. Pseudo NMOS Inverter
7. Dynamic Inverter
8. Transmission gate based inverter

4. Select correct ones from the following statements:

- i) As the skew ratio,  $\gamma$  increases, NML decreases and NMH increases.
- ii) As the skew ratio,  $\gamma$  increases, NML increases and NMH decreases.
- iii) As the skew ratio,  $\gamma$  decreases, NML decreases and NMH increases.
- iv) As the skew ratio,  $\gamma$  decreases, NML increases and NMH decreases.

1. Only i, ii, iii
2. Only i
3. **Only ii, iii**
4. Only iv
5. Only ii, iv
6. Only iii
7. Only i, iii
8. All of the above

5. A particular logic family has  $V_{OH} = 5V$ ,  $V_{OL} = 1V$ ,  $V_{IH} = 3.5V$  and  $V_{IL} = 2V$ . The noise margin values NMH and NML will be

1. **1.5V, 1V**
2. 2V, 1V
3. 0.5V, 1V
4. 1V, 1V
5. 1V, 1.5V
6. 1.5V, 1.5V
7. 2V, 2V
8. 0.5V, 0.5V

$$NM_H = V_{OH} - V_{IH}$$

$$NM_L = V_{IL} - V_{OL}$$

**Solution:-**

6. Find  $V_{OH}$  and  $V_{IL}$  for an ideal transistor given the following metrics:

$$\beta_{NMOS} = \beta_{PMOS}$$

$$V_{DD} = 1V$$

$$V_{t,PMOS} = -0.3V$$

$$V_{t,NMOS} = 0.3V$$

1.  $V_{OH} = 0.75V$   $V_{IL} = 0.45V$
2.  $V_{OH} = 0.65V$   $V_{IL} = 0.45V$
3.  **$V_{OH} = 0.95V$   $V_{IL} = 0.45V$**
4.  $V_{OH} = 0.9V$   $V_{IL} = 0.45V$
5.  $V_{OH} = 0.95V$   $V_{IL} = 0.15V$
6.  $V_{OH} = 0.95V$   $V_{IL} = 0.25V$
7.  $V_{OH} = 0.95V$   $V_{IL} = 0.35V$
8.  $V_{OH} = 0.85V$   $V_{IL} = 0.45V$

$$I_{ds_{NMOS\ sat}} = I_{sd_{PMOS\ Linear}}$$

**Solution:-**

7. For 65 nm technology node,  
 $W = 1\mu m$

$L = 50\text{nm}$   
 $t_{ox} = 1.05\text{nm}$   
 $\epsilon_{ox} = 3.9 \times 8.854 \times 10^{-14} \text{ F/cm}$   
 $C_{Load} = 20 \text{ fF}$   
 $V_{DD} = 1\text{V}$   
 $V_{t,PMOS} = -0.3\text{V}$   
 $V_{t,NMOS} = 0.3\text{V}$   
 $V_{dt} = V_{DD} - V_t$   
 Saturation velocity for nMOS =  $10^7 \text{ cm/s}$   
 $V_c = 1.04\text{V}$   
 $\mu = 80\text{cm}^2/\text{v-sec}$  and short channel model. Find  $t_{pdf}$ .

1.  $t_{pdf} = 5.79\text{ps}$
2.  $t_{pdf} = 5.22\text{ps}$
3.  $t_{pdf} = 8.66\text{ps}$
4.  $t_{pdf} = 7.24\text{ps}$
5.  **$t_{pdf} = 10.79\text{ps}$**
6.  $t_{pdf} = 8.01\text{ps}$
7.  $t_{pdf} = 6.76\text{ps}$
8.  $t_{pdf} = 11.98\text{ps}$

**Solution:-**

$$t_{pdf} = \frac{(V_{dd} - V_t + V_c) C_{Load} (V_{dd}/2)}{W C_{ox} (V_{dd} - V_t)^2 v_{sat}}$$

$$t_{pdf} = \frac{1.74 \times 20 \text{ fF} \times 0.5}{10^{-4} \times 3.9 \times 8.854 \times 10^{-14} \times 0.7^2 \times 10^7}$$

$$t_{pdf} = 10.79 \text{ ps}$$

**Short Channel Current model**

8. For  $k = 2$ , the Switching resistances and diffusion capacitances are ( $R$  = switching resistance of unit NMOS;  $C$  = diffusion capacitance of unit NMOS):

1.  $R_{NMOS} = R/4$ ;  $R_{PMOS} = R/2$ ;  $C_{NMOS} = C/4$ ;  $C_{PMOS} = C/2$
2.  $R_{NMOS} = R/2$ ;  $R_{PMOS} = R/4$ ;  $C_{NMOS} = C/2$ ;  $C_{PMOS} = C/4$
3.  $R_{NMOS} = 4R$ ;  $R_{PMOS} = 2R$ ;  $C_{NMOS} = 4C$ ;  $C_{PMOS} = 2C$
4.  $R_{NMOS} = 2R$ ;  $R_{PMOS} = 4R$ ;  $C_{NMOS} = 2C$ ;  $C_{PMOS} = 4C$
5.  **$R_{NMOS} = R/2$ ;  $R_{PMOS} = R$ ;  $C_{NMOS} = 2C$ ;  $C_{PMOS} = 2C$**

6. RN MOS = R/2; RP MOS = R/4; CN MOS = 2C; CP MOS = 2C
7. RN MOS = 4R; RP MOS = 2R; CN MOS = C/4; CP MOS = C/4
8. RN MOS = 2R; RP MOS = 4R; CN MOS = C/2; CP MOS = C/2

9. For Switching resistance = 2K $\Omega$ , Capacitance = 20fF, what is the RC approximation delay?

1. 6.93ps
2. 13.86ns
3. 13.86ps
4. 27.72ms
5. **27.72ps**
6. 27.72ns
7. 13.86ms
8. 6.93ns

**Solution:-**

$$0.693 \cdot R \cdot C$$

10. For 65 nm technology node,

$$W = 1\mu\text{m}$$

$$L = 50\text{nm}$$

$$t_{ox} = 1.05\text{nm}$$

$$\epsilon_{ox} = 3.9 \times 8.854 \times 10^{-14} \text{ F/cm}$$

$$C_{Load} = 20 \text{ fF}$$

$$V_{DD} = 1\text{V}$$

$$V_{t,PMOS} = -0.3\text{V}$$

$$V_{t,NMOS} = 0.3\text{V}$$

$$V_{dt} = V_{DD} - V_t$$

$\mu = 80\text{cm}^2/\text{v-sec}$  and long channel model. Find  $t_{pdf}$ .

1.  $t_{pdf} = 7.72\text{ns}$
2.  **$t_{pdf} = 7.72\text{ps}$**
3.  $t_{pdf} = 7.72\text{ms}$
4.  $t_{pdf} = 15.44\text{ps}$
5.  $t_{pdf} = 15.44\text{ns}$
6.  $t_{pdf} = 15.44\text{ms}$
7.  $t_{pdf} = 3.86\text{ps}$
8.  $t_{pdf} = 3.86\text{ns}$

**Solution:-**

$$\beta_N = \mu C_{ox} \frac{W}{L} = \frac{80 \times 3.9 \times 8.854 \times 10^{-14}}{1.05 \times 10^{-7}} \times \frac{10^{-4}}{50 \times 10^{-7}} = 5.26 \times 10^{-3}$$

$$t_{sat} = \frac{2 \times 20 \times 10^{-15} \times 0.3}{5.26 \times 10^{-3} \times 0.7^2} = 4.55 \text{ ps}$$